



# 11/B

Box AF 1/22/03  
Expedited Procedure Muller  
Examining Group 2813  
Docket No. 740819-634

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of: )  
Koji ARITA et al. ) Group Art Unit: 2813  
Application No.: 09/938,528 ) Examiner: David S. BLUM  
Filed: 08/27/2001 )  
For: METHOD FOR MANUFACTURING A )  
SEMICONDUCTOR DEVICE )

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**AMENDMENT**

Commissioner for Patents  
Washington, D.C. 20231  
ATTN: **BOX AF**

Sir:

In response to the Office Action mailed September 11, 2002, the due date for which having been extended one (1) month to January 11, 2003, please amend the above identified application as follows.

**IN THE CLAIMS:**

Please amend claim 1 as follows:

- SUB  
C1 7
- B1
1. (Twice Amended) A method for manufacturing a semiconductor device, comprising the steps of:
- forming, in a semiconductor layer formed on a first insulating film, an element isolation groove extending to the first insulating film;
  - depositing a second insulating film so as to partially fill the element isolation groove by using a vapor deposition method;
  - forming an embedded layer on the second insulating film so as to completely fill the element isolation groove; and
  - forming a third insulating film on the embedded layer,